

# Latest Technology in Thin Film Measurements

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LEYBOLD OPTICS

- **Motivation (Requirements of good measurement equipment)**
- **Features of new Dual In Situ Sensor**
- **Experimental results**
- **Summary**

## Main reasons for development of DISS:

- Increase productivity
  - Reduce scrap
  
- Increase product quality
  - Reduce tolerances

# Requirements for good measurement equipment

To avoid scrap

**online** quality control equipment must enable the operator

- To detect **all** quality relevant deviations
  - To detect them **accurately** and **immediately**
    - To take corrective action **fast**
      - Verify success of corrective action in **real time**

→ **minimize** the time constant for loop control

## **Threats** for scrap (accessible to DISS)

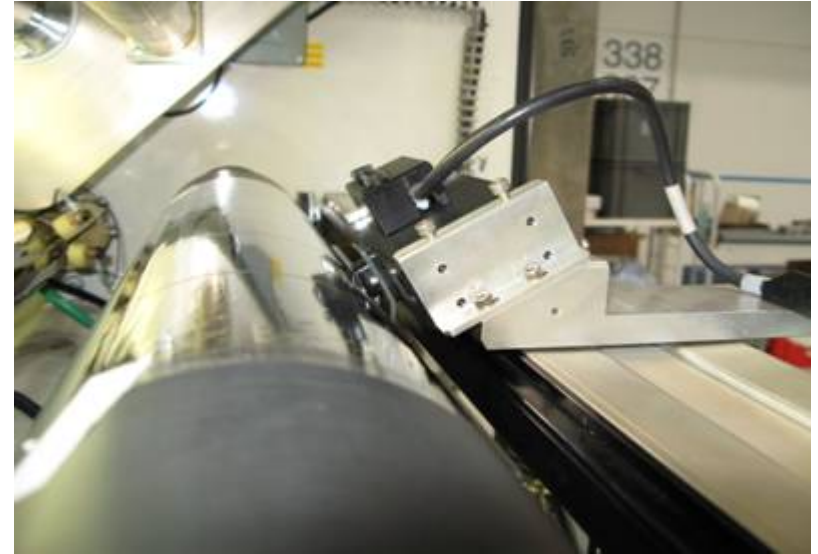
- Absolute values for
  - layer thickness of active area **and** heavy edge
  - Width of free margins
- Uniformity across **and** along the web for
  - layer thickness of active area **and** heavy edge
  - Width of free margins
- Alignment of heavy edge, free margins and pattern

# Conventional Measurement Equipment



Free Margin Measurement System

- Traveling sensors across web width
- Supply only one information at a time
- Uniformity information across web takes up to 60 sec. (1200 m of web)
- Return time after corrective action up to 60 sec. (1200 m of scrap)



Layer Measurement System LMS

**Needed is simultaneous, real time measurement  
of all quality relevant parameters !**

# Example: Pattern

## Layer Thickness of Patterned Film:

- Present equipment restricted to pattern sizes of  $> 15 \times 15$  mm
- Trend towards smaller structures
- Smaller probe area required
- DISS supplies resolution for pattern structures down to  $3 \times 3$  mm<sup>2</sup>

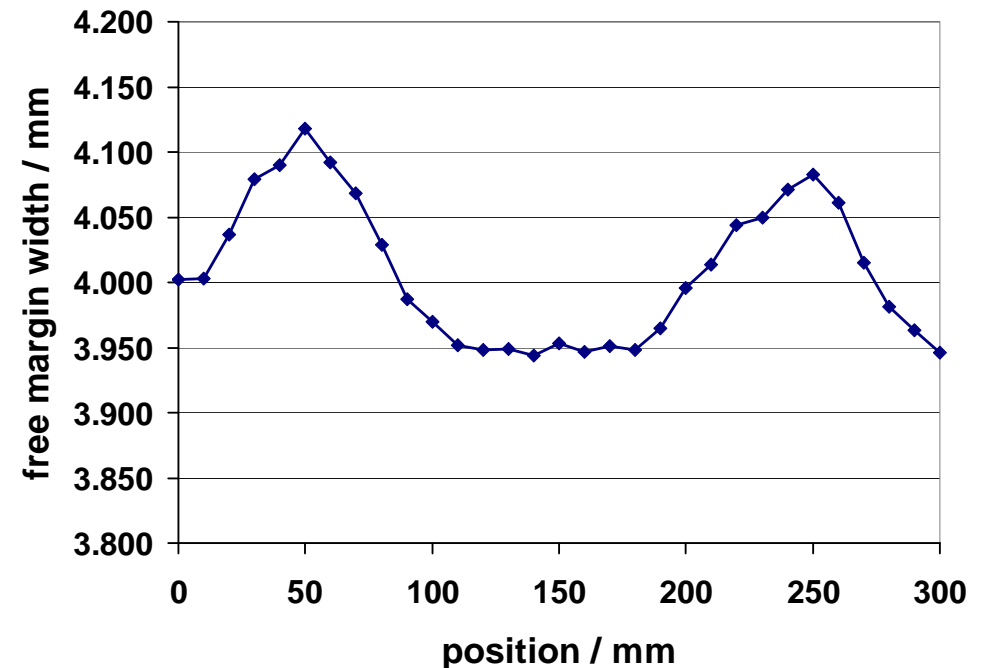


# Example: Free margin uniformity

## Oscillating free margins

- Resolution of free margin measurement 20 to 200 m of web between readings
- Free margin oscillations go unnoticed
- Required is a resolution  $< 0.2$  m to detect free margin oscillations
- DISS supplies resolution of 0.003 m

Width of free margin **along** the Web

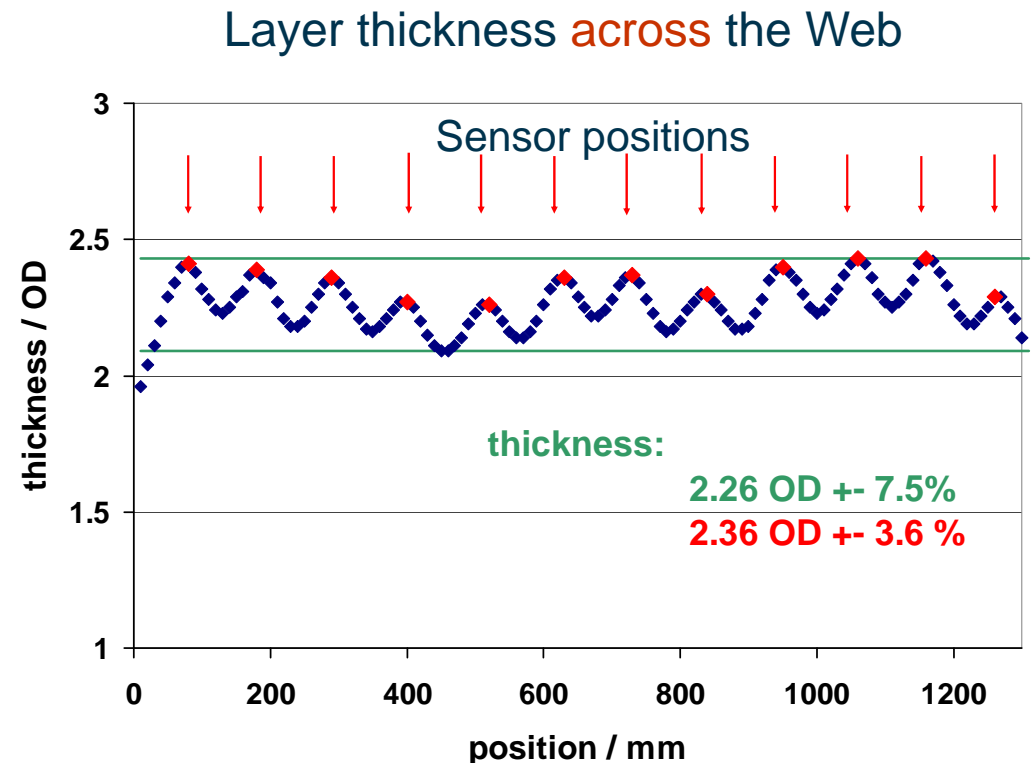




# Example: Uniformity across Web

## Banding:

- Present equipment measures only few positions
- Ignores variations between measurement points
- Resulting uniformity information too tolerant
- Higher spatial resolution of sensors needed: Nyquist theorem
- DISS supplies spatial resolution of  $< 3$  mm

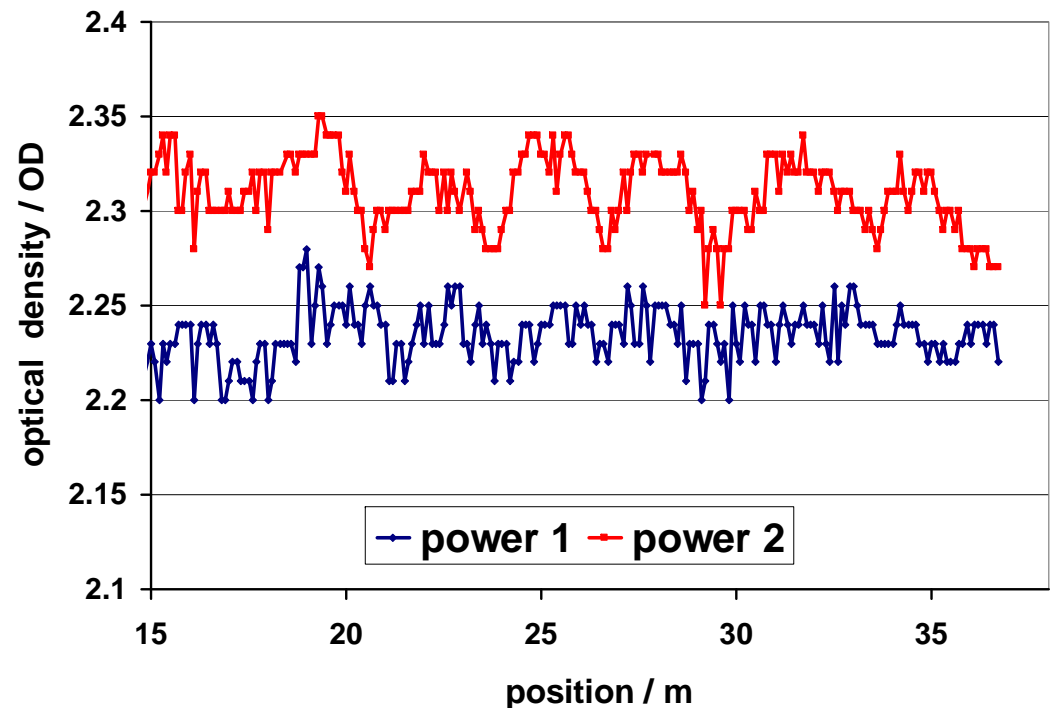


# Example: Uniformity along Web

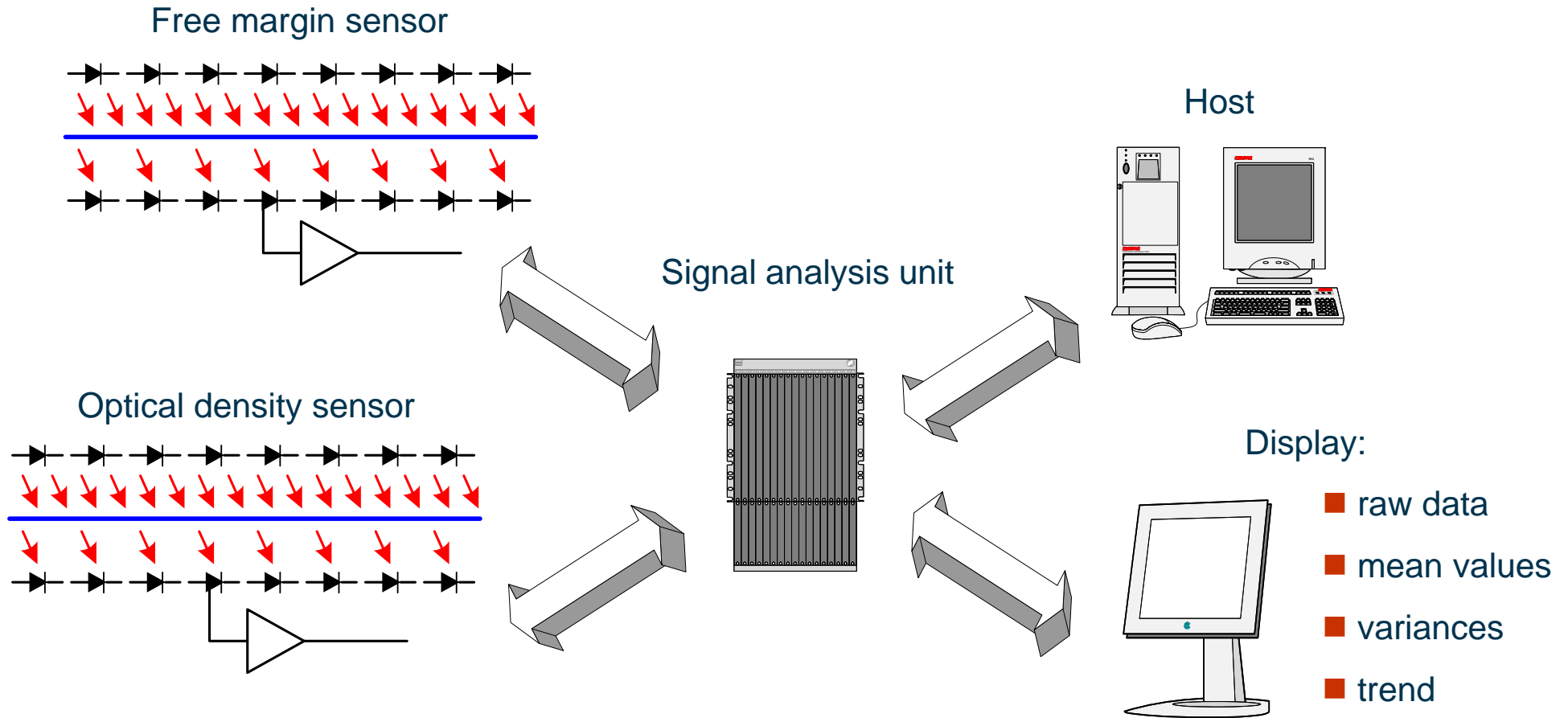
## AI-Dripping:

- Present equipment measures every ~ 100 m web length
- Cannot detect variations between measurement points
- Resulting Nonuniformity is “Noise”
- Higher measurement frequency needed
- DISS supplies frequency of 20 kHz corresponding to 1 mm @ 20 m/sec

Layer thickness **along** the WEB



# DISS, Principle



# DISS, the bare FACTS

## Optical Density Sensor

Parameter	Unit	DISS-Spec
Optical density	OD	0 - 4
Wavelength	nm	645
Geometrical resolution across web	mm	3
Geometrical resolution along web @ 20m/s	mm	3
Probe Frequency	kHz	20

## Free Margin Sensor

Parameter	Unit	DISS-Spec
Optical resolution across web	$\mu\text{m}$	< 50
Geometrical resolution along web @ 20 m/s	mm	3
Probe Frequency	kHz	20

# Comparison

## What **DISS** can see for YOU

Parameter	Capability	Real Time
Average Layer Thickness in Active Area and Heavy Edge	yes	yes
Uniformity of Layer Thickness across Web	yes	yes
Uniformity of Layer Thickness along Web	yes	yes
Width of Free Margins	yes	yes
Uniformity of Free Margins across Web	yes	yes
Uniformity of Free Margins along Web	yes	yes
Alignment of Heavy Edges and Free Margins	yes	yes

## Conventional

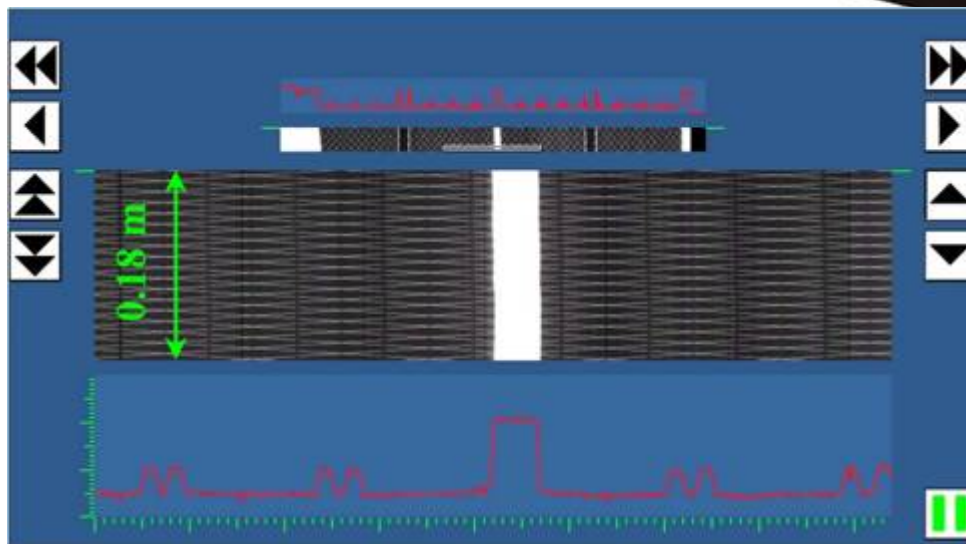
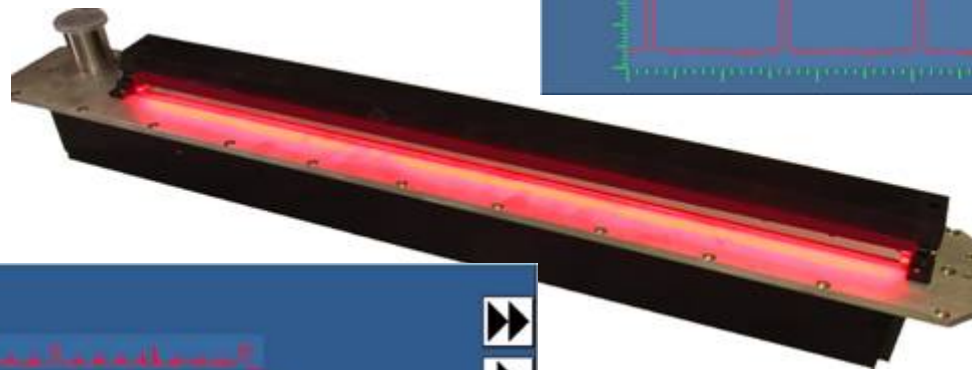
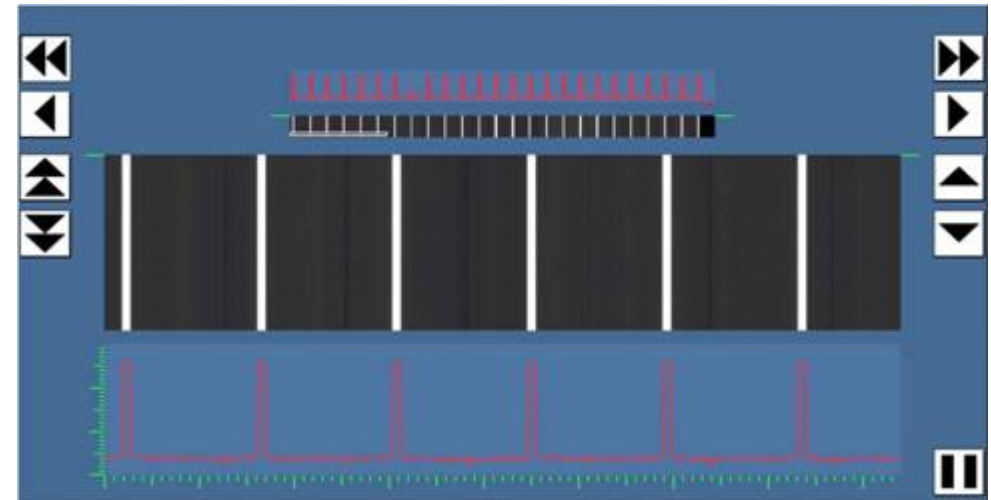
Capability	Real Time
yes	no
yes	no
no	no
yes	no
yes	no
no	no
no	no

# DISS: Experimental Results

Free margin measurement:

free margin: 0.5 mm

pitch: 9 mm



Free margin measurement:

free margin: 4.0 mm

pattern: 8 x 8 mm<sup>2</sup>

winding speed: ~ 18 m/s

# Summary

- Scrap reduction by true real time process control
- All free margins are measured simultaneously
- Real time control of layer uniformity across **and** along the web
- '100%' quality control of the film
- Online control of the alignment of free margin, active area/heavy edge and pattern (for capacitor applications)
- Online control of layer thickness for patterned capacitor films
- DISS is the basic prerequisite for improvements in automatic layer control and the automatic uniformity control
- No moving parts, simple adjustment, auto calibration for thickness measurement

**Thank you for your kind attention !**